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S Magoshi, H Niiyama, S Sato, Y Kato, Y Watanabe, ... - Jpn. J. Appl. Phys, 1999 - jjap.ipap.jp

... **Shunko Magoshi**, Hiromi Niiyama, Shinji Sato, Yoshimitsu Kato, Yumi Watanabe, Tohru ...Fabricating Sub-100-nm Complementary Metal-Oxide-**Semiconductor** Devices using ...Cited by 1 - [Cached](#) - [Web Search](#) - [BL Direct](#)

### High-speed electron beam data conversion system combining hierarchical operation with parallel ... - group of 2 »

S Magoshi, K Koyama, O Ikenaga, S Watanabe, T ... - JPN J APPL PHYS PART 1 REGUL PAP SHORT NOTE., 1992 - csa.com

**Shunko Magoshi**, Kiyomi Koyama, Osamu Ikenaga, Susumu Watanabe, Tamaki Saito, ShinjiSakamoto, Shin-ichiro ... 2 **Semiconductor** Devices and Integrated Circuits; E 932 ...[Web Search](#) - [BL Direct](#)

### Throughput Enhancement Strategy of Maskless Electron Beam Direct Writing for Logic Device - group of 2 »

R Inanami, S Magoshi, S Kousai, M Hamada, T ... - INTERNATIONAL ELECTRON DEVICES MEETING, 2000 - ieeexplore.ieee.org

... Ryoichi Inanami, **Shunko Magoshi**, Shohei Kousai", Mototsugu Hamada", ToshinariTakayanagi ... bess & Manufacturing Engineering Center, **Semiconductor** Company, Toshiba ...[Web Search](#) - [BL Direct](#)

### Stress-Induced Voiding Phenomena for an actual CMOS LSI Interconnects

H NAKAZAWA, M MORITA - ieeexplore.ieee.org

... **Semiconductor** Company. ... Ms. Sachiyo Itoh. Mr. **Shunko Magoshi**, and Mr. Masayuki Hatano

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Nakasugi, T.; Ando, A.; Inanami, R.; Sasaki, N.; Sugihara, K.;  
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31 Oct.-2 Nov. 2001 Page(s):302 - 303  
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- ☐ 3. **Throughput enhancement strategy of maskless electron beam direct write device**  
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- ☐ 4. **Lithography simulator for EB/DUV Intra-level mix and match**  
Inanami, R.; Nakasugi, T.; Sato, S.; Mimotogi, S.; Tanaka, S.; Sugihara, K.;  
[Microprocesses and Nanotechnology Conference, 1999. Digest of Papers. Mic](#)  
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[VLSI Technology, 2004. Digest of Technical Papers. 2004 Symposium on 15-17 June 2004 Page\(s\):84 - 85](#)  
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[Electron Devices Meeting, 2002. IEDM '02. Digest. International 8-11 Dec. 2002 Page\(s\):639 - 642](#)  
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[Electron Devices Meeting, 2001. IEDM Technical Digest. International 2-5 Dec. 2001 Page\(s\):29.6.1 - 29.6.4](#)  
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[Microprocesses and Nanotechnology Conference, 1998 International](#)  
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- ☐ **6. Charge Reducing Effect Of Chemically Amplified Resist**  
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